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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.		
09/512,942	02/25/2000	THEODORE H. FEDYNYSHYN	101328-148	6865		
21125	7590 12/26/2001					
	NUTTER MCCLENNEN & FISH LLP			EXAMINER		
BOSTON, MA	NATIONAL PLACE A 02110	CHU, JOHN S Y				
			ART UNIT	PAPER NUMBER		
			1752	8		
			DATE MAILED: 12/26/2001			

Please find below and/or attached an Office communication concerning this application or proceeding.

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``		Application No.		Applicant(s)		
Office Action Summary		09/512,942	F	FEDYNYSHYN, THEODORE H.		
		Examiner	1	Art Unit		
		John S. Chu		1752	Idross	
Period fo					aress	
THE N - Exter after - If NO - Failu - Any n	ORTENED STATUTORY PERIOD FOR REPL MAILING DATE OF THIS COMMUNICATION. Assions of time may be available under the provisions of 37 CFR 1.1 SIX (6) MONTHS from the mailing date of this communication. Period for reply specified above is less than thirty (30) days, a reple period for reply is specified above, the maximum statutory period re to reply within the set or extended period for reply will, by statute eply received by the Office later than three months after the mailined patent term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however ly within the statutory minin will apply and will expire SI	er, may a reply be timel num of thirty (30) days v X (6) MONTHS from th secome ABANDONED	y filed vill be considered time e mailing date of this o (35 U.S.C. § 133).	ely. communication.	
1)	Responsive to communication(s) filed on 27	November 2001 .				
2a)⊠	•	his action is non-fin	al.			
3)	Since this application is in condition for allow closed in accordance with the practice under	vance except for for FEx parte Quayle,	mal matters, pro 1935 C.D. 11, 45	secution as to t 3 O.G. 213.	he merits is	
Disposit	ion of Claims					
4)⊠	Claim(s) 1-17 is/are pending in the application					
	4a) Of the above claim(s) 18-21 is/are withdra	wn from considerat	ion.			
5) 🗌	Claim(s) is/are allowed.					
6)⊠	Claim(s) <u>1-17</u> is/are rejected.					
	Claim(s) is/are objected to.					
8) 🗌	Claim(s) are subject to restriction and/	or election requiren	nent.			
Applicat	ion Papers					
	The specification is objected to by the Examin					
10)	The drawing(s) filed on is/are: a) acc	epted or b)⊡ objecte	ed to by the Exan	niner.		
	Applicant may not request that any objection to t					
11)	The proposed drawing correction filed on			/ed by the Exam	iner.	
	If approved, corrected drawings are required in r		ion.			
,	The oath or declaration is objected to by the E	xaminer.				
	under 35 U.S.C. §§ 119 and 120			(-1) (O		
1	Acknowledgment is made of a claim for foreign	gn priority under 35	U.S.C. § 119(a)	-(a) or (t).		
a	n All b) Some * c) None of:					
	1. Certified copies of the priority document			N		
	2. Certified copies of the priority documen				al Stago	
*	 Copies of the certified copies of the pri application from the International E See the attached detailed Office action for a list 	Bureau (PCT Rule 1	7.2(a)).		ai Stage	
141	Acknowledgment is made of a claim for domes	stic priority under 3	5 U.S.C. § 119(e	e) (to a provision	nal application).	
	a) The translation of the foreign language p Acknowledgment is made of a claim for dome	rovisional applicati	on has been rec	eived.		
Attachme	nt(s)	_				
2) Not	ice of References Cited (PTO-892) ice of Draftsperson's Patent Drawing Review (PTO-948) rmation Disclosure Statement(s) (PTO-1449) Paper No(s)	4)	Interview Summary Notice of Informal F Other:			
U.S. Patent and	Trademark Office			Pa	rt of Paner No. 8	

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DETAILED ACTION

This Office action is in response to the amendment received November 27, 2001 and the IDS received December 6, 2001.

1. Newly submitted claim18-21 are directed to an invention that is independent or distinct from the invention originally claimed for the following reasons: The new claims are drawn to a process for patterning or processing a semiconductor substrate using the composition as recited in claim 1. These new claims are distinct from the claimed composition such that the claimed composition can be used in a materially different process such as a process for forming parts or structures by cast molding, thus providing a burden to the examiner to additionally consider the method claims.

Since applicant has received an action on the merits for the originally presented invention, this invention has been constructively elected by original presentation for prosecution on the merits. Accordingly, claim18-21 are withdrawn from consideration as being directed to a non-elected invention. See 37 CFR 1.142(b) and MPEP § 821.03.

- 2. The rejection under 35 U.S.C. 102(b) as being anticipated by USHIROGOUCHI ET AL is withdrawn in view of the amendment to claim 1 reciting the particle size of the core particles.

 USHIROGUCHI ET AL lacks the claimed particles size having an average size less than 10 nm.
- 3. The rejection under 35 U.S.C. 102(b) as being anticipated by MAINTHIA is withdrawn in view of the amendment to claim 1 reciting the particle size of the core particles. MAINTHIA lacks the claimed particles size having an average size less than 10 nm.

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4. The rejection under 35 U.S.C. 102(e) as being anticipated by DENZINGER ET AL. is withdrawn in view of the amendment to claim 1 reciting the particle size of the core particles.

DENZINGER ET AL lacks the claimed particles size having an average size less than 10 nm.

- 5. The rejection under 35 U.S.C. 102(e) as being anticipated by ELSAESSER ET AL is withdrawn in view of the amendment to claim 1 reciting the particle size of the core particles. ELSAESSER ET AL lacks the claimed particles size having an average size less than 10 nm.
- 6. The rejection under 35 U.S.C. 103(a) as being unpatentable over OTA ET AL. is withdrawn in view of the amendment to claim 1 reciting the particle size of the core particles.

 OTA ET AL lacks the claimed particles size having an average size less than 10 nm.

Claim Rejections - 35 USC § 103

- 7. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 8. Claims 1-17 rejected under 35 U.S.C. 103(a) as being unpatentable over KAWAMURA ET AL.

The claimed invention is drawn to a positive photosensitive resist composition comprising a resin binder and an encapsulated inorganic material.

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KAWAMURA ET AL discloses a photosensitive composition comprising a resin binder and inorganic particles as seen in column 25, lines 24 – 55 wherein the particles are present in an amount of 2 to 90% by volume.

KAWAMURA ET AL lacks the specific use of alumina or titanium dioxide in an explicit example.

It would have been *prima facie* obvious to one of ordinary skill in the art of photosensitive compositions to use either of alumina or titanium dioxide and reasonably expect same or similar results as those compositions which have improved sensitivity and discrimination.

Motivation is based on the desire to provide good sensitivity and contrast.

The arguments have been carefully considered, however applicants are further directed to column 30, lines 44-52 wherein the size of surface-modified particles fall in the range of 1 nm to 2000 nm. This disclosed range motivates the skilled artisan to use particles having those sizes disclosed wherein the end points serve at actual data points suitable for use. Thus KAWAMURA ET AL provides clear motivation for the skilled artisan to use particles having sizes are recited in claim 1 being less than 10 nm. Further the composition of KAWAMURA ET AL is also base soluble even if it not explicitly disclosedm because compositions developed by water, which are basic to the acid -produced compositions upon exposure, would also be developable in a stronger basic compound therefore inherently meeting the claimed invention.

9. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

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A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

10. Any inquiry concerning this communication or earlier communications from the examiner should be directed to John S. Chu whose telephone number is (703) 308-2298. The examiner can normally be reached on M-F from 9:30 am to 6:00 pm.

The fax phone number for the organization where this application or proceeding is assigned is (703) 305-3599.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0661.

John S. Chu

Primary Examiner, Group 1700

J.Chu

December 20, 2001